Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S7	54	("cyclic organosiloxane") film "low dielectric constant"	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/02/27 09:31
S11	13	("cyclic organosiloxane").clm. and ((film or coat\$3) with (low near3 (k or dielectric))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/22 11:22
S12	140	("20010051445" "20020037442" "2 0020074309" "20020098714" "2002 0142585" "20020160626" "2002018 0051" "20020197849" "2003000899 8" "20030017718" "20030040195" " 20030064154" "20030104689" "200 30104708" "20030109236" "200301 11712" "20030116421" "200301760 30" "20030198742" "20030211244" "20030211728" "20030224593" "2 0030232137" "20040076764" "2004 0096593" "20040096672" "2004010 1632" "20040101633" "4945054" "5 000113" "5003178" "5786990" "59899 98" "6051321" "6054379" "6057251 " "6068884" "6080526" "6159871" "6271146" "6303047" "6312793" "6 316083" "6340628" "6352945" "638 3955" "6410463" "6432846" "64374 43" "6441491" "6444136" "6455445 " "6479110" "6479408" "6500773" "6509259" "6514880" "6524974" "6 548899" "6582777" "6583048" "65936 55" "6596627" "6605549" "6627532 " "6673725" "6677253" "6734533" "6 737365").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/22 13:01
S14	11	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")).clm. and ((("N.sub.2" adj O) or (nitrous adj oxide)) and (oxygen or ("O.sub. 2"))).clm. and ((low near3 (k or dielectric)) with (film or coat\$3)). clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 14:58

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S15	7	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")).clm. and ((("N.sub.2" adj O) or (nitrous adj oxide))).clm. and ((low near3 (k or dielectric)) with (film or coat\$3)). clm. not S11	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/22 15:31
S17	163	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")) and ((("N. sub.2" adj O) or (nitrous adj oxide)) and (oxygen or ("O.sub.2"))) and ((low near3 (k or dielectric)) with (film or coat\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/22 16:28
S18	155	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")) and ((("N. sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub.2"))) and ((low near3 (k or dielectric)) with (film or coat\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/22 16:30
S19	45	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")) and ((("N. sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub.2"))).clm. and ((low near3 (k or dielectric)) with (film or coat\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/22 17:45
S21	60	((("N.sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub. 2")) same ((oxidiz\$5 and (gas\$3 or vapor or stream) and (ratio or fraction or percent\$3 or proportion) and (flowrate or rate or velocity)))) and (CVD or "chemical vapor deposition" or (vapor adj deposit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 10:57
S22	5	((("N.sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub. 2")) same ((oxidiz\$5 and (gas\$3 or vapor or stream) and (ratio or fraction or percent\$3 or proportion) and (flowrate or rate or velocity)))) and (CVD or "chemical vapor deposition" or (vapor adj deposit\$4)) and (\$10siloxane)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/22 18:38

S23	10	((("N.sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub. 2")) same ((oxidiz\$5 and (gas\$3 or vapor or stream) and (ratio or fraction or percent\$3 or proportion) and (flowrate or rate or velocity)))) and (CVD or "chemical vapor deposition" or (vapor adj deposit\$4)) and ("low dielectric" or "low k")	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 12:48
S24	313	(((("N.sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub. 2"))) same (oxidiz\$5 and (gas\$3 or vapor or stream))) and (CVD or "chemical vapor deposition" or (vapor adj deposit\$4)) and ("low dielectric" or "low k")	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 13:05
S25	163	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")) and ((("N. sub.2" adj O) or (nitrous adj oxide)) and (oxygen or ("O.sub.2"))) and ((low near3 (k or dielectric)) with (film or coat\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 13:06
S26	155	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")) and ((("N. sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub.2"))) and ((low near3 (k or dielectric)) with (film or coat\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 13:06
S27	45	((cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$)) or ("cyclic organosiloxane")) and ((("N. sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub.2"))).clm. and ((low near3 (k or dielectric)) with (film or coat\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 13:06
S28	60	((("N.sub.2" adj O) or (nitrous adj oxide)) with (oxygen or ("O.sub. 2")) same ((oxidiz\$5 and (gas\$3 or vapor or stream) and (ratio or fraction or percent\$3 or proportion) and (flowrate or rate or velocity)))) and (CVD or "chemical vapor deposition" or (vapor adj deposit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON .	2007/03/26 13:06

S31	11	(cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$ or organosiloxane)).clm. and ((("N. sub.2" adj O) or (nitrous adj oxide)) and (oxygen or ("O.sub.2"))).clm. and ((low near3 (k or dielectric)) with (film or coat\$3)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/10 17:44
S32	20	(cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$ or organosiloxane)).ab,clm. and ((("N. sub.2" adj O) or (nitrous adj oxide)) and (oxygen or ("O.sub.2"))).ab, clm. and ((low near3 (k or dielectric)) with (film or coat\$3)). ab,clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/26 15:13
S47	12	(cyclic and (\$tetrasilox\$ or \$pentasilox\$ or \$trisilox\$ or organosiloxane)).clm. and (("N.sub. 2" adj O) or (nitrous adj oxide)). clm. and (low near3 (k or dielectric)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/27 15:49
S54	125	(("e-beam" or (electron adj beam)) with (\$4treat\$4 or cur\$3)) same (film with ("low k" or (low adj dielectric)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/04/10 17:46